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Substitute for form 1449/PTO

Complete if Known Substitute for form 1449/PTO Application Number 10/799,073 Filing Date 12 March 2004 INFORMATION DISCLOSURE First Named Inventor Michel Luc Cole STATEMENT BY APPLICANT Art Unit 1756 (Use as many sheets as necessary) Examiner Name Unassigned Sheet 1 Attorney Dockot Number NMTI 1002-26 of 1 U. S. PATENT DOCUMENTS Name of Patentee or Cile No. **Document Number** Publication Date Pagas, Columns, Lines, Where MM-DD-YYYY Applicant of Cited Document Roceant Passages or Relevant Number-Kind Code<sup>2 (3 h</sup> US- 6,040,892 A1 03-21-2000 Pierrat UŞ US ŪS ŪS-USus US US US-US-US-118 US. US-US FOREIGN PATENT DOCUMENTS Examine Initials Foreign Pubmit Ducament Name of Palentee or Piges, Citianns, Lines, Where Relevant Passages Date Applicant of Cited Document Or Relevant Figures Appear Country Code<sup>3</sup> "Number <sup>4</sup> "Kirel Code<sup>5</sup> (Elascent) Examinor
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<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup> Applicant is to place a check mark here if English language Translation is ettached.

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